

AMENDMENTS TO THE CLAIMS

1-8. (Canceled)

9. (Currently Amended) A coating method of forming a coating film on a surface of a substrate by making a coating liquid which is raised by capillary phenomenon in a nozzle ~~into~~ contact with the surface and ~~make~~ making the raised coating liquid be coated on the surface by the relative movement of the nozzle and the substrate,

comprising:

holding the substrate by a holding means so that the surface to be coated by the coating liquid faces downward;

bringing the holding means and a chucking means toward each other by moving at least one of the holding means and the chucking means, maintaining the surface to be coated facing downward;

chucking the substrate by the chucking means;

separating the holding means and a chucking means away from each other by moving at least one of the holding means and the chucking means; and

forming the coating film on the surface to be coated of the substrate by moving at least one of the nozzle and the chucking means in a horizontal direction,

wherein the holding means turns by a predetermined angle to make the substrate held in an inclined state, for attaching and detaching the substrate to and from the holding means.

10. (previously presented) The coating method of claim 9 wherein, after said forming, the substrate is released from the chucking means in a state that a coated surface of the substrate faces downward.

11. (previously presented) The coating method of Claim 9 wherein the chucking is carried out by vacuum means.

12. (previously presented) The coating method of Claim 9 wherein during the forming of the coating film on the surface, controlling a distance between the nozzle and the surface so that the film thickness is uniform.

13. (previously presented) The coating method of Claim 9 wherein before said forming, the nozzle is lifted so that the coating liquid is brought into contact with the surface, and the nozzle is descended an amount to determine a coating thickness.

14. (canceled)

15. (previously presented) The coating method of claim 9, wherein the coating film comprises a photo-resist.

16. (previously presented) The coating method of claim 9, wherein the substrate comprises a photo mask blank.

17. (currently amended) A method of manufacturing a photo mask blank having a photo resist coating film on a surface, which film is formed, on a substrate, by making a coating liquid which is raised by capillary phenomenon in a nozzle ~~into~~ contact with the surface and making the raised coating liquid be coated on the surface by the relative movement of the nozzle and the substrate,

the method comprising:

holding the substrate by a holding means so that the surface to be coated by the coating liquid faces downward;

bringing the holding means and a chucking means toward each other by moving at least one of the holding means and the chucking means, maintaining the surface to be coated facing downward;

chucking the substrate by the chucking means; and

separating the holding means and the chucking means away from each other by moving at least one of the holding means and the chucking means; and

forming the coating film on the surface to be coated of the substrate by moving at least one of the nozzle and the chucking means in a horizontal direction,

wherein, for attaching and detaching the substrate to and from the holding means, the holding means turns by a predetermined angle to make the substrate held in an inclined state.

18. (new) The coating method of Claim 1 wherein the substrate is sized so that at least one side has a length of 300 mm.

19. (new) The method of Claim 17, wherein the substrate is sized so that at least one side has a length of 300 mm.

20. (new) The coating method of claim 9, further comprising absorbing shock in the holding means when the holding means and the chucking means are moved in an up-and-down direction with respect to one another.

21. (New) The coating method of claim 17, further comprising absorbing shock in the holding means when the holding means and the chucking means are moved in an up-and-down direction with respect to one another.